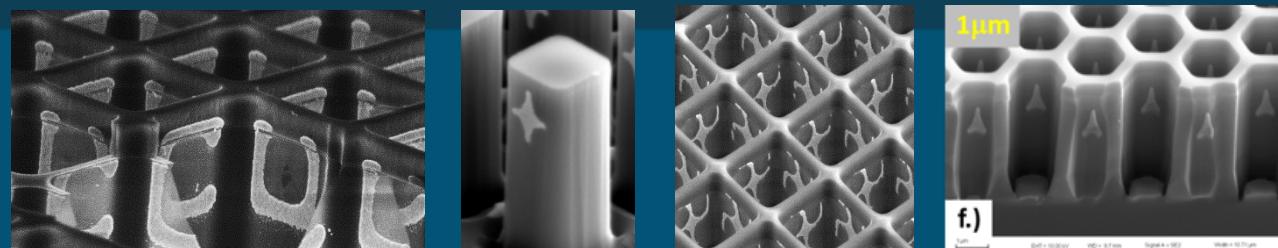




Sandia
National
Laboratories

Coupling to Slab Modes in Suspended 3D Optical Metafilms



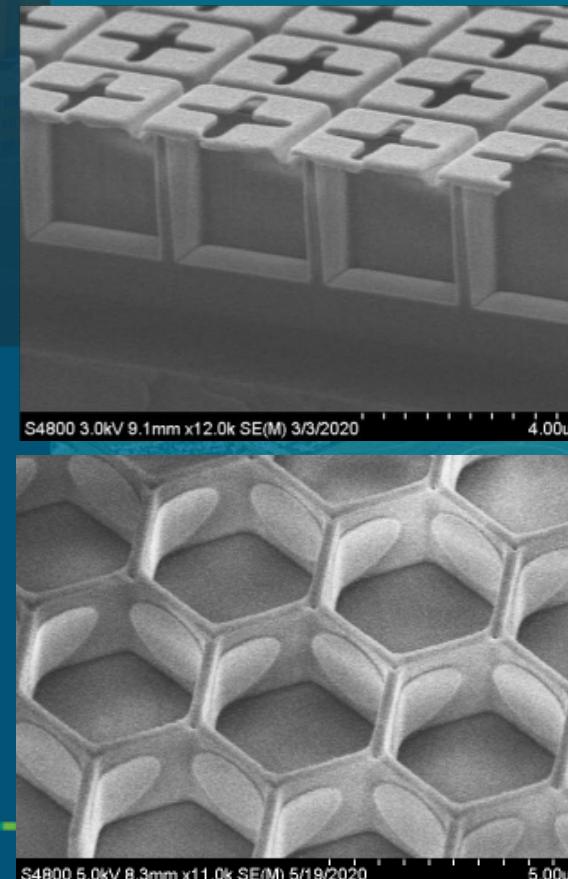
Katherine M. Musick and D. Bruce Burckel

dbburck@sandia.gov

EIPBN 2022

New Orleans, Louisiana

June 1, 2022



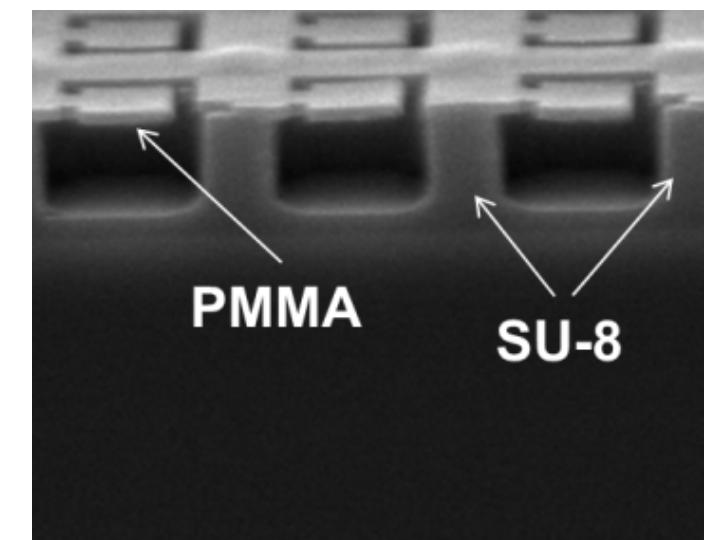
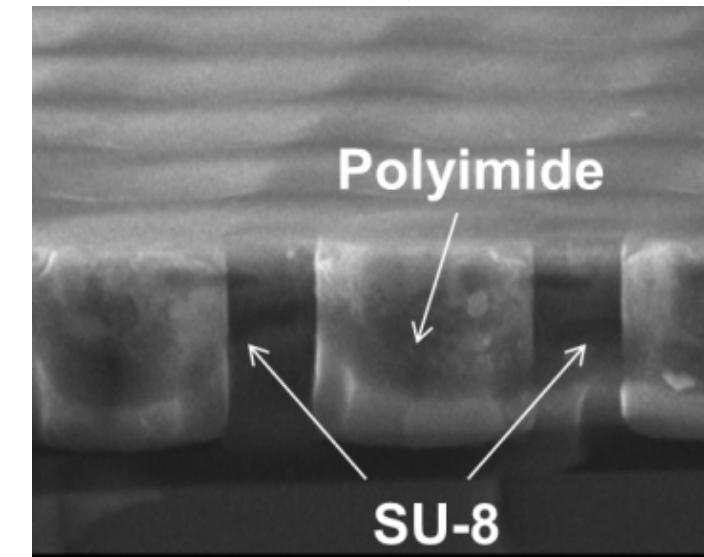
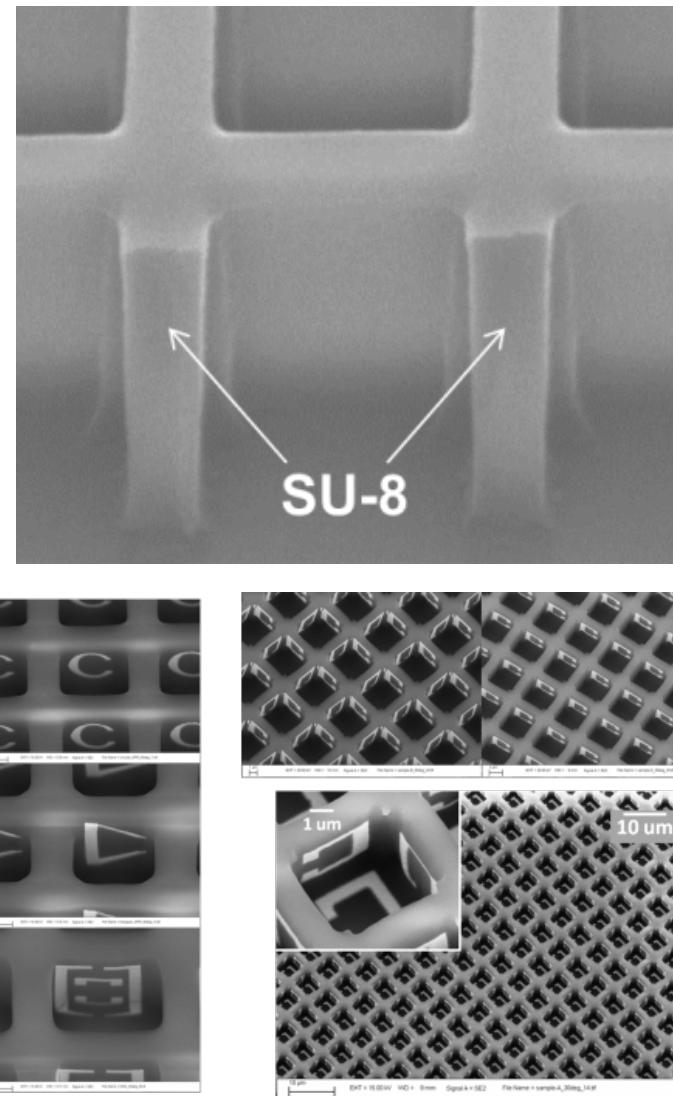
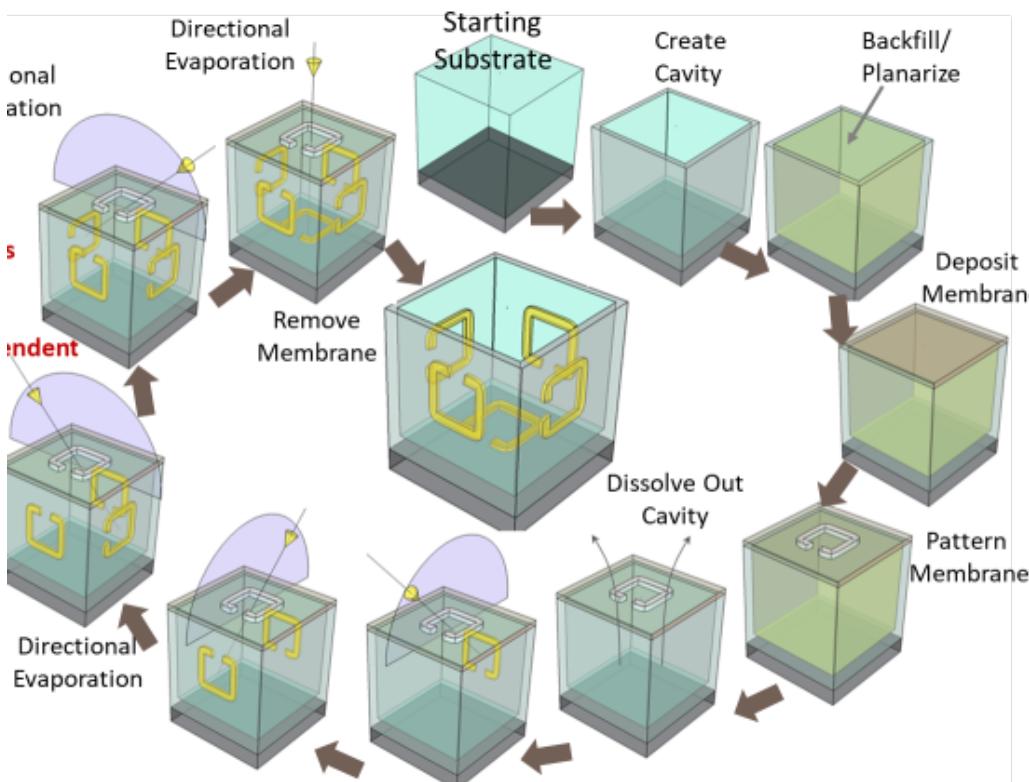
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- 1.3D Metafilm Fabrication via membrane projection lithography (MPL)
2. Periodically modulated dielectric matrix – photonic crystal slab modes
3. Coupling between plasmonic resonances and photonic crystal slab modes

Membrane Projection Lithography

DB Burckel et. al., "Micrometer-scale cubic unit cell 3D metamaterials"
Adv. Mater. **22** 5053-5057 (2010).

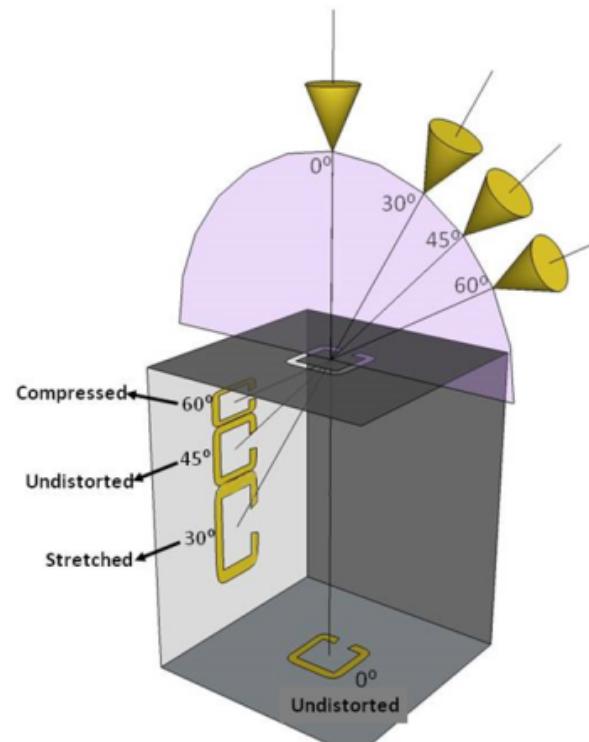
Polymer-Based Membrane Projection Lithography (2009)



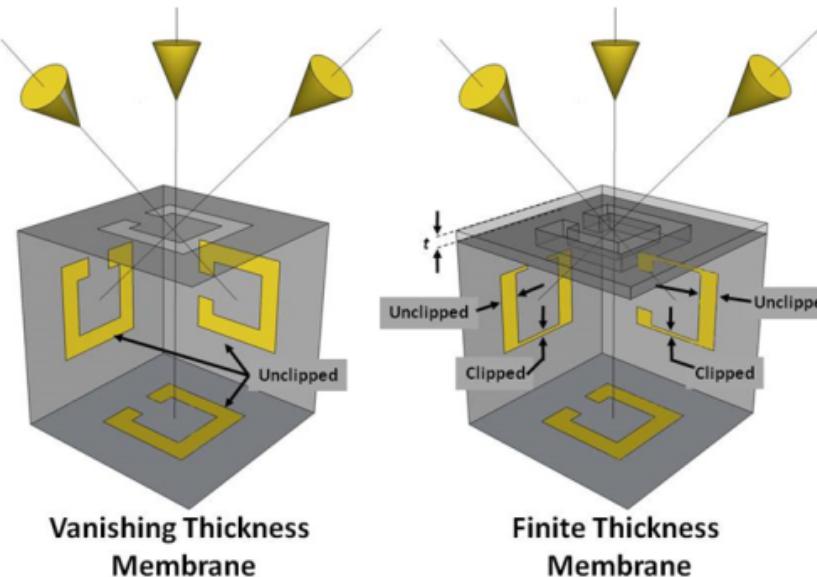
Sources of MPL Pattern Distortion



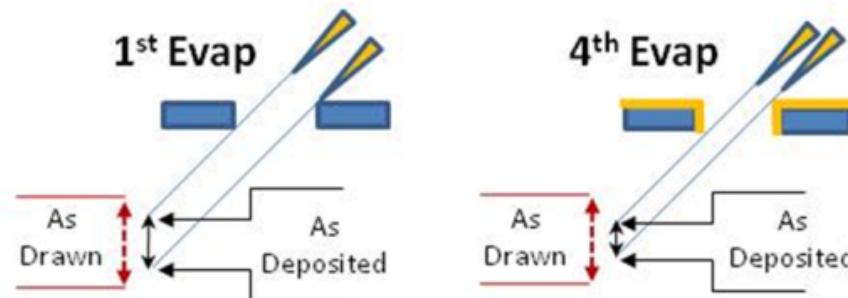
Projection at 45°
Preserves Pattern
Shape in Cubic Geometries



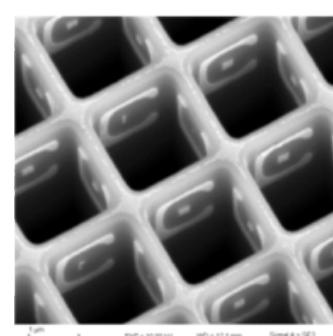
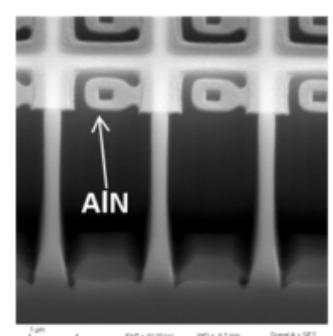
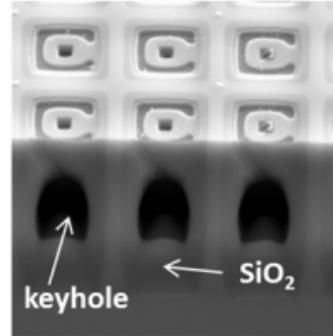
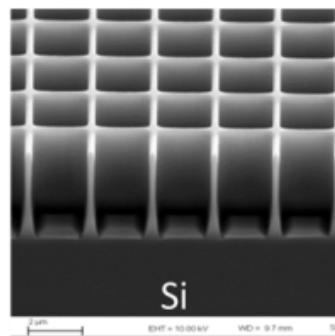
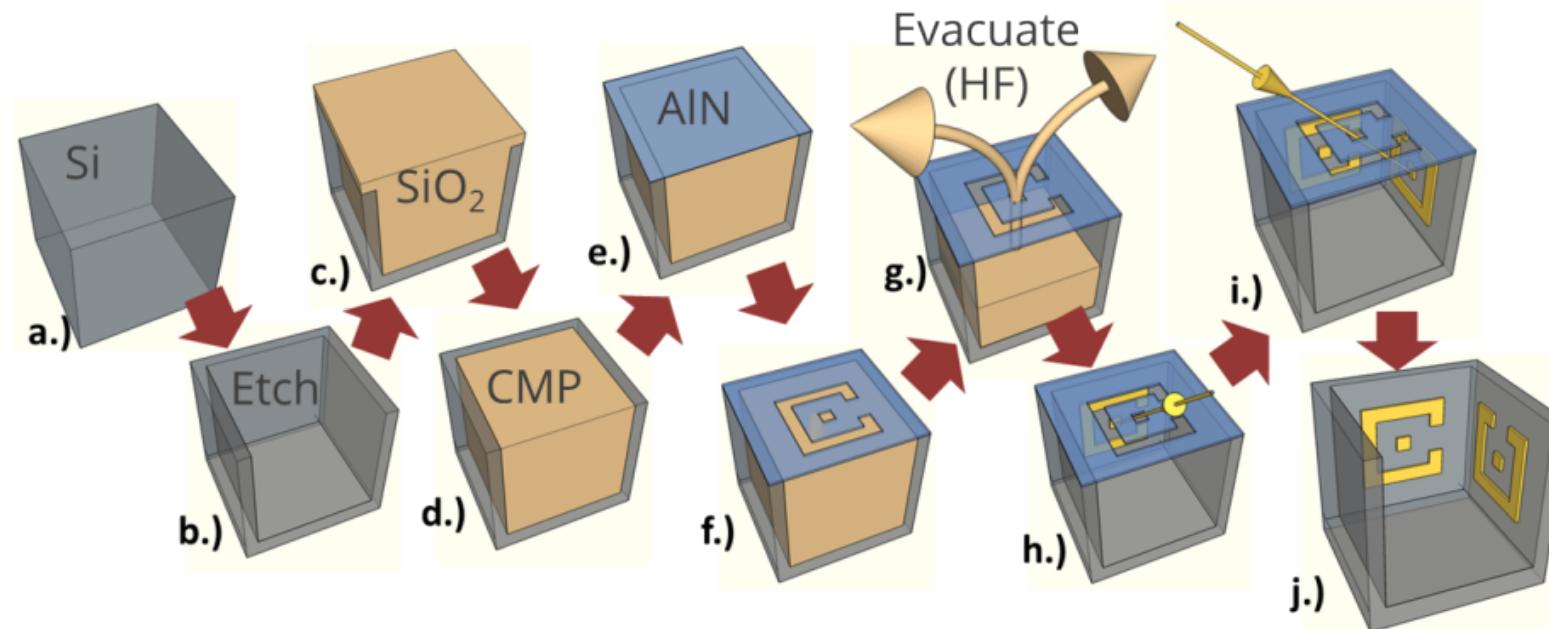
Real Membranes result in Linewidth Clipping



Multiple Evaporations result in Linewidth Thinning

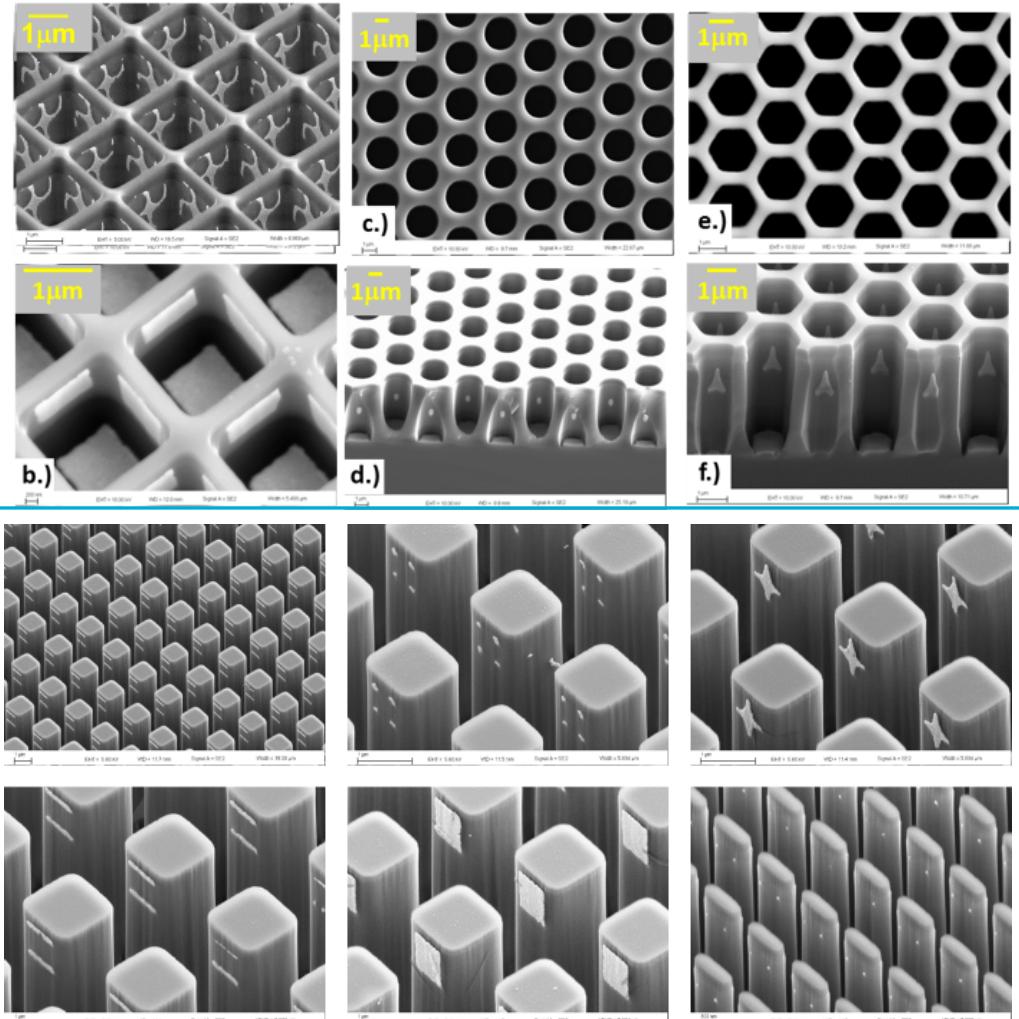


CMOS Compatible MPL (2015)

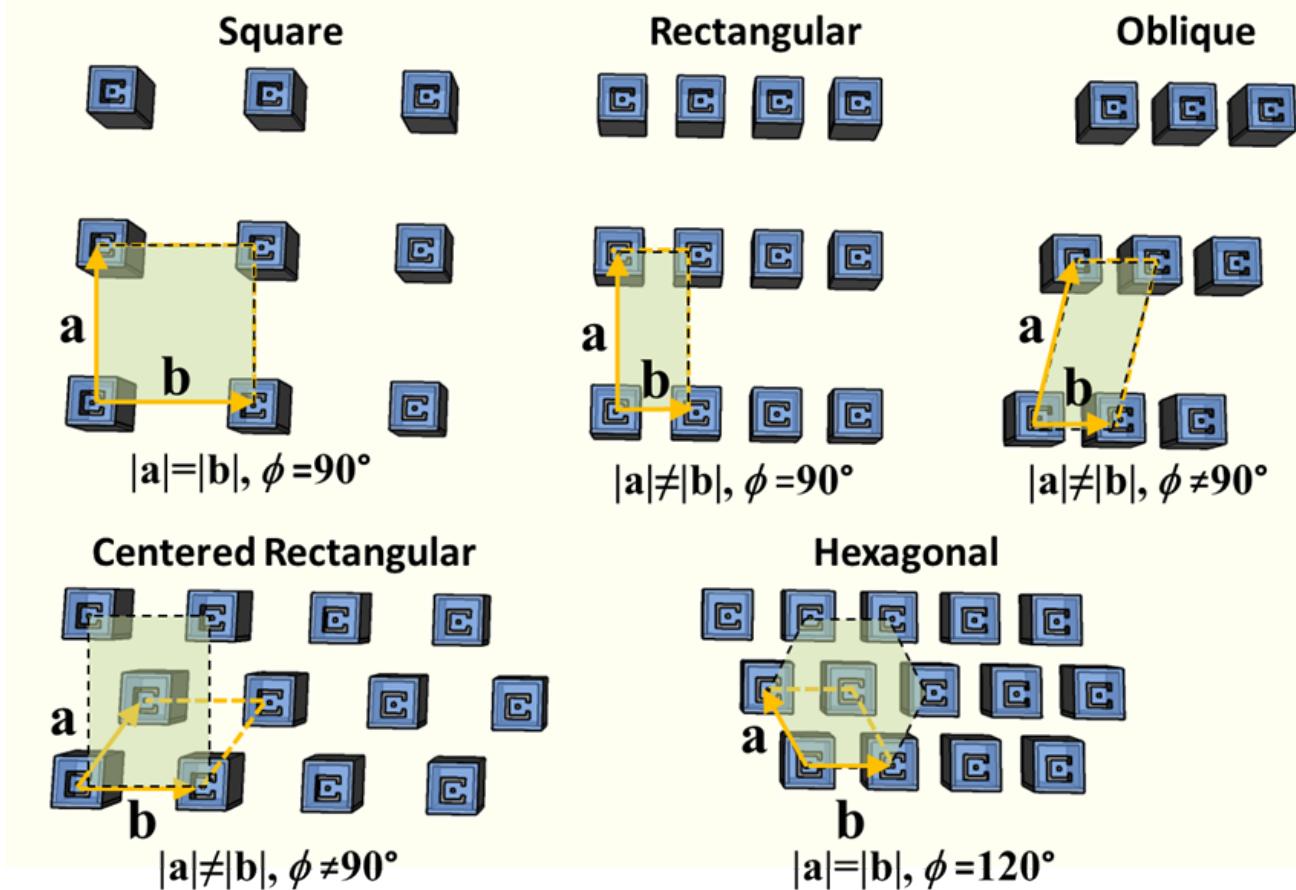


DB Burckel et. al., "Micrometer-scale fabrication of complex 3D lattice + basis structures in silicon"
Opt Mat.. Exp. **10** , 2231-2239 (2015).

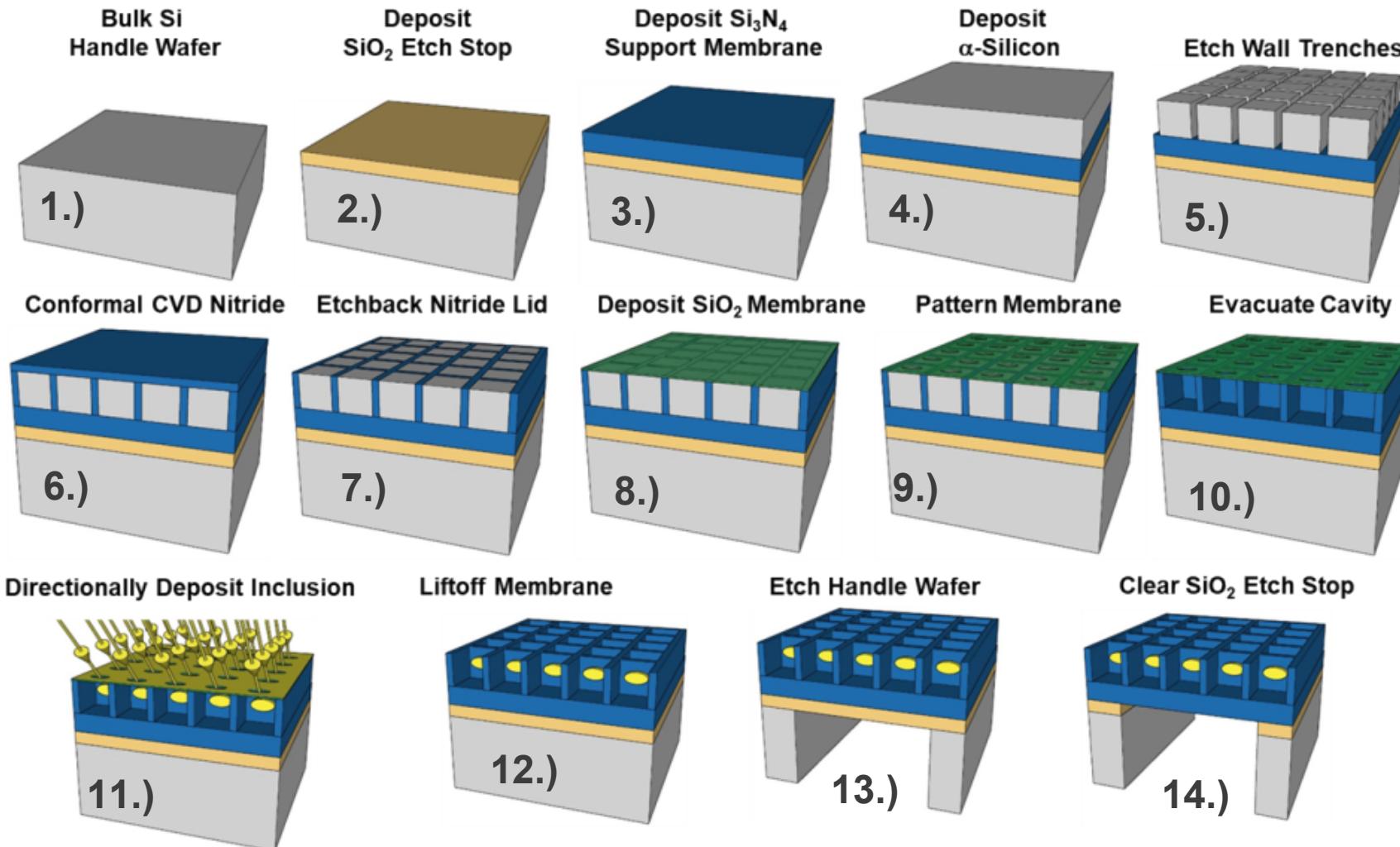
3D micron-scale Metamaterials



Any In-plane Lattice



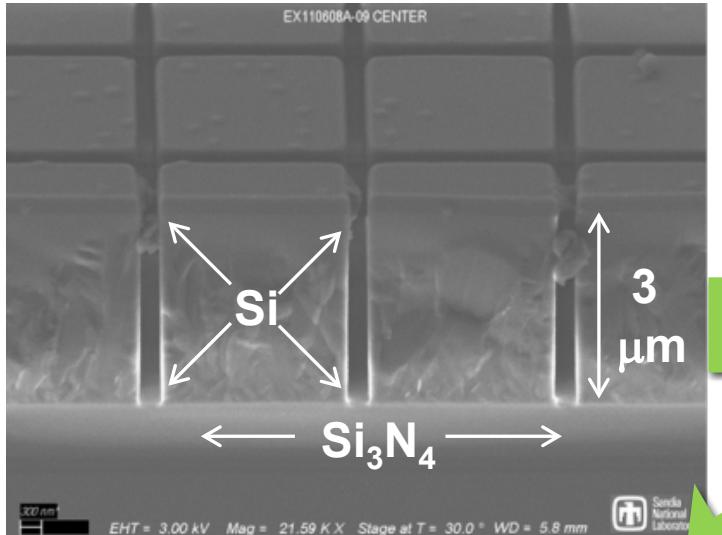
Wall-First Membrane Projection Lithography Process Flow (2020)



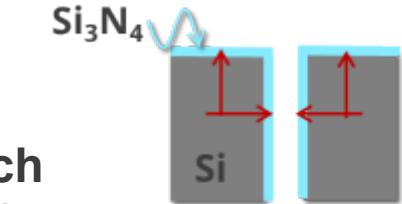
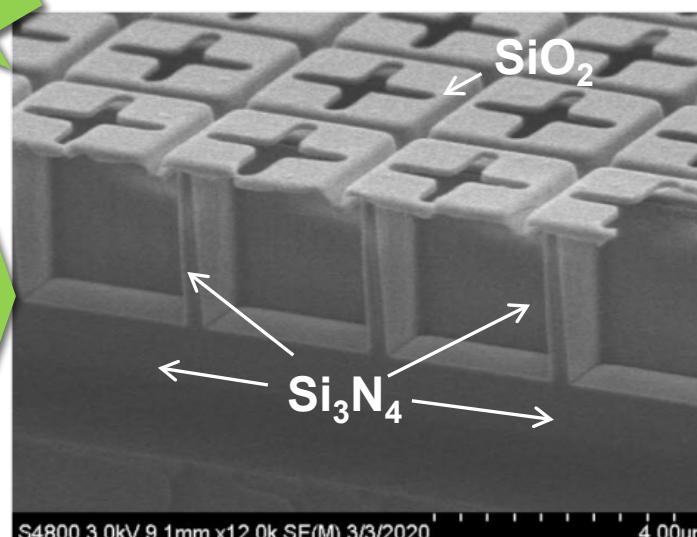
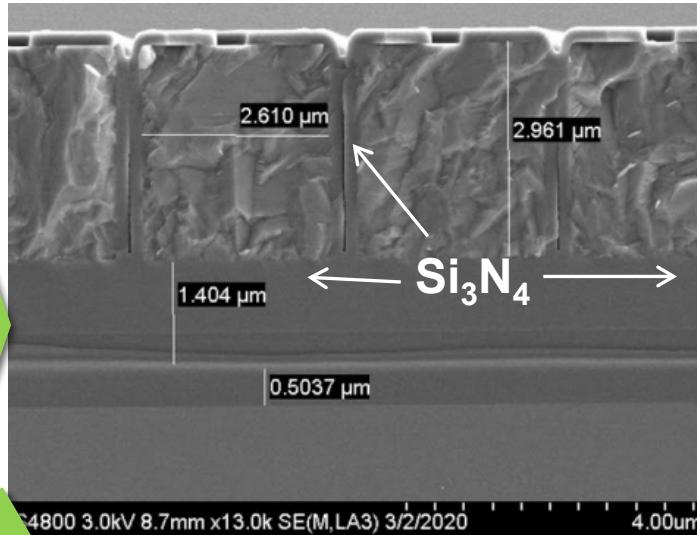
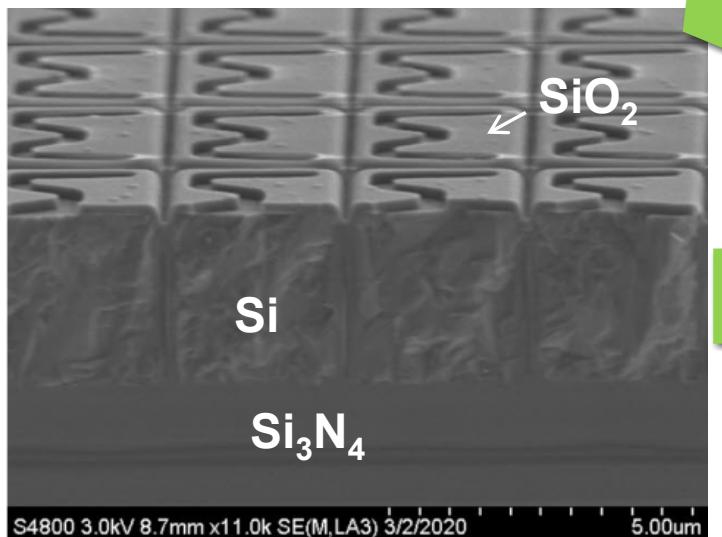
Process Flow Snapshot SEMs



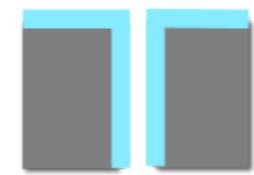
Trench Etch



Membrane Patterning

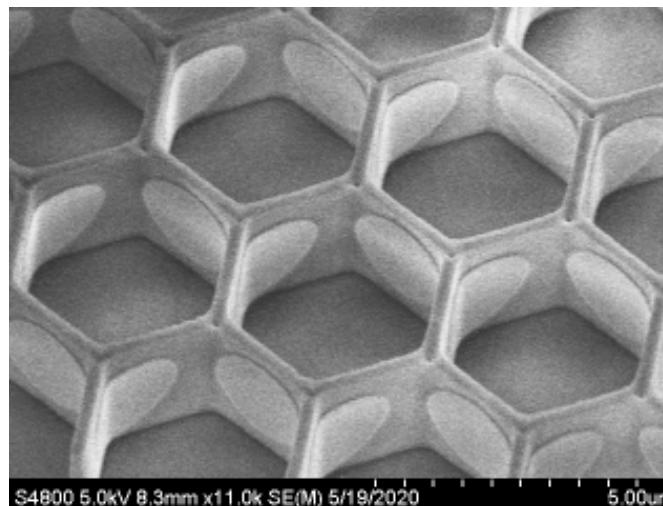
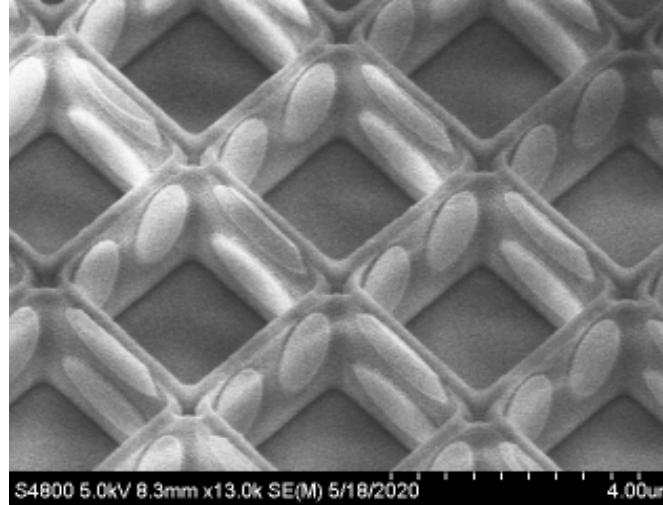
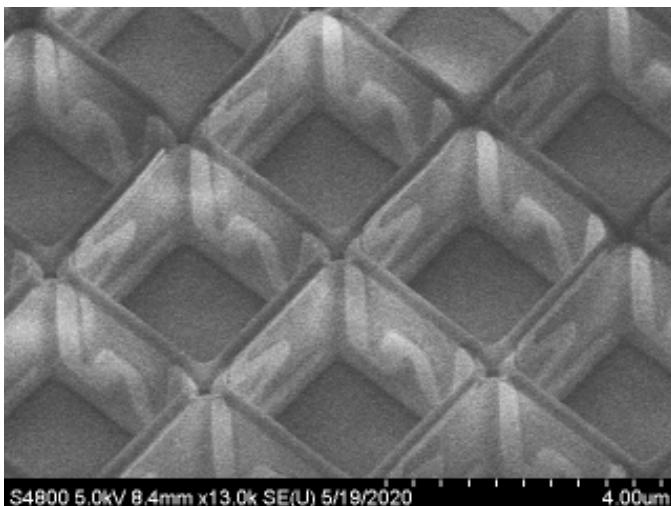
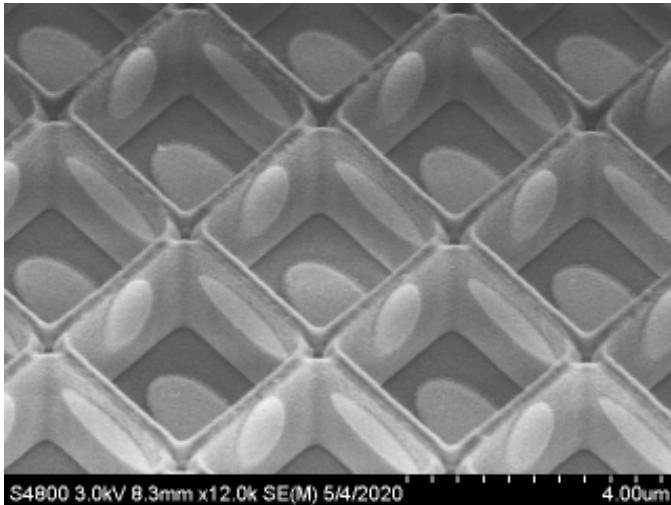


Trench Backfill

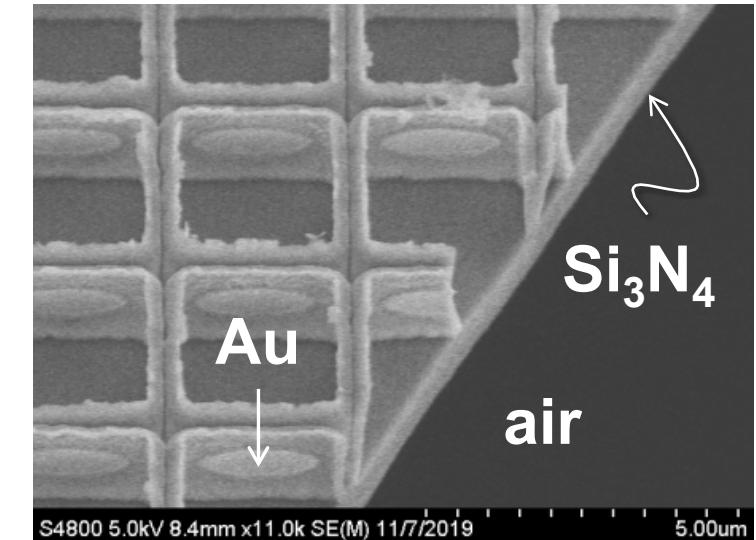


Cavity Evacuation (XeF_2)

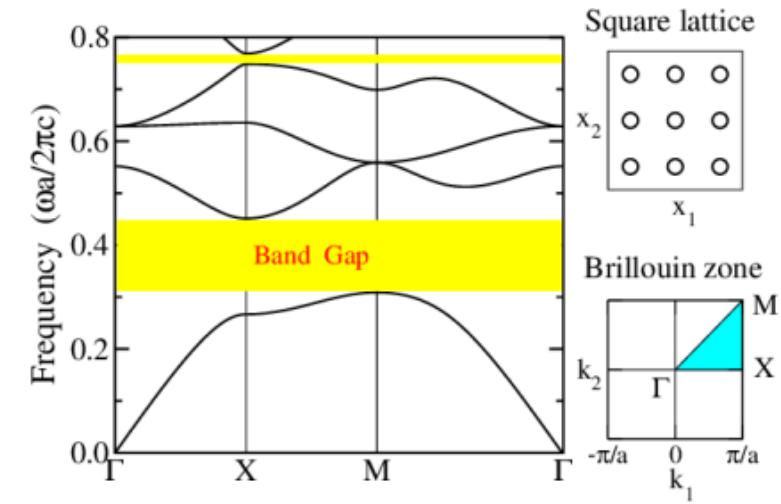
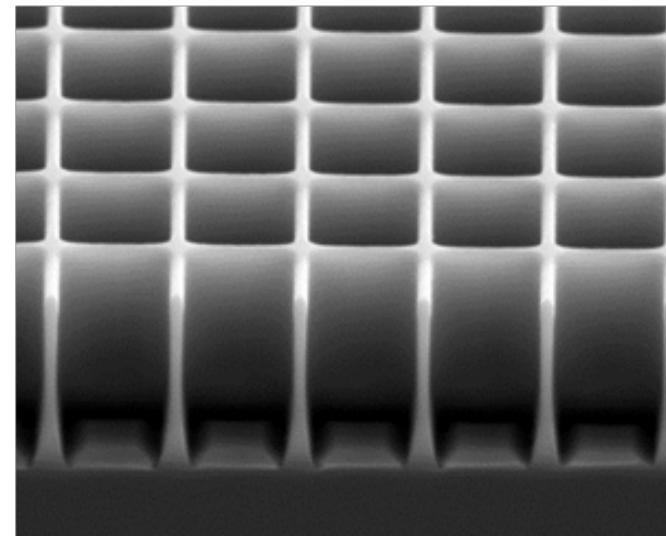
Decorated Unit Cells – 3D Metafilms



Handle Wafer Removed

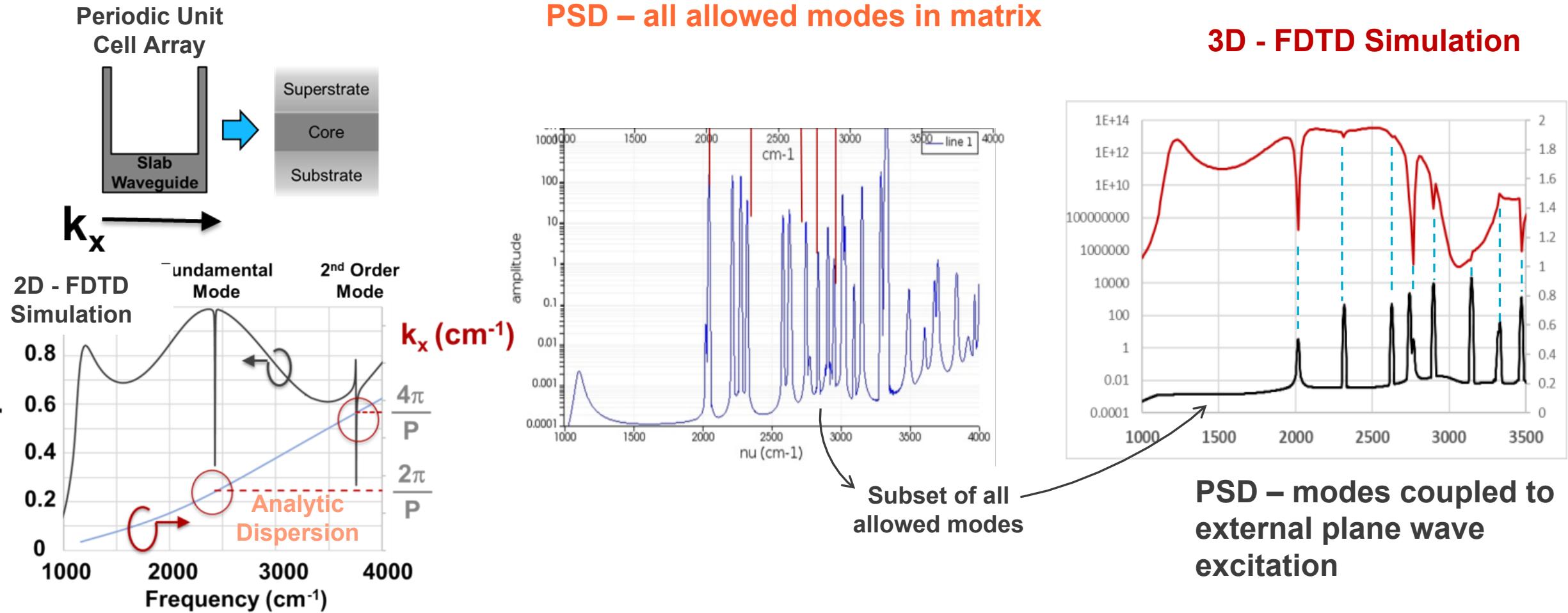


Photonic Crystal Slab Modes

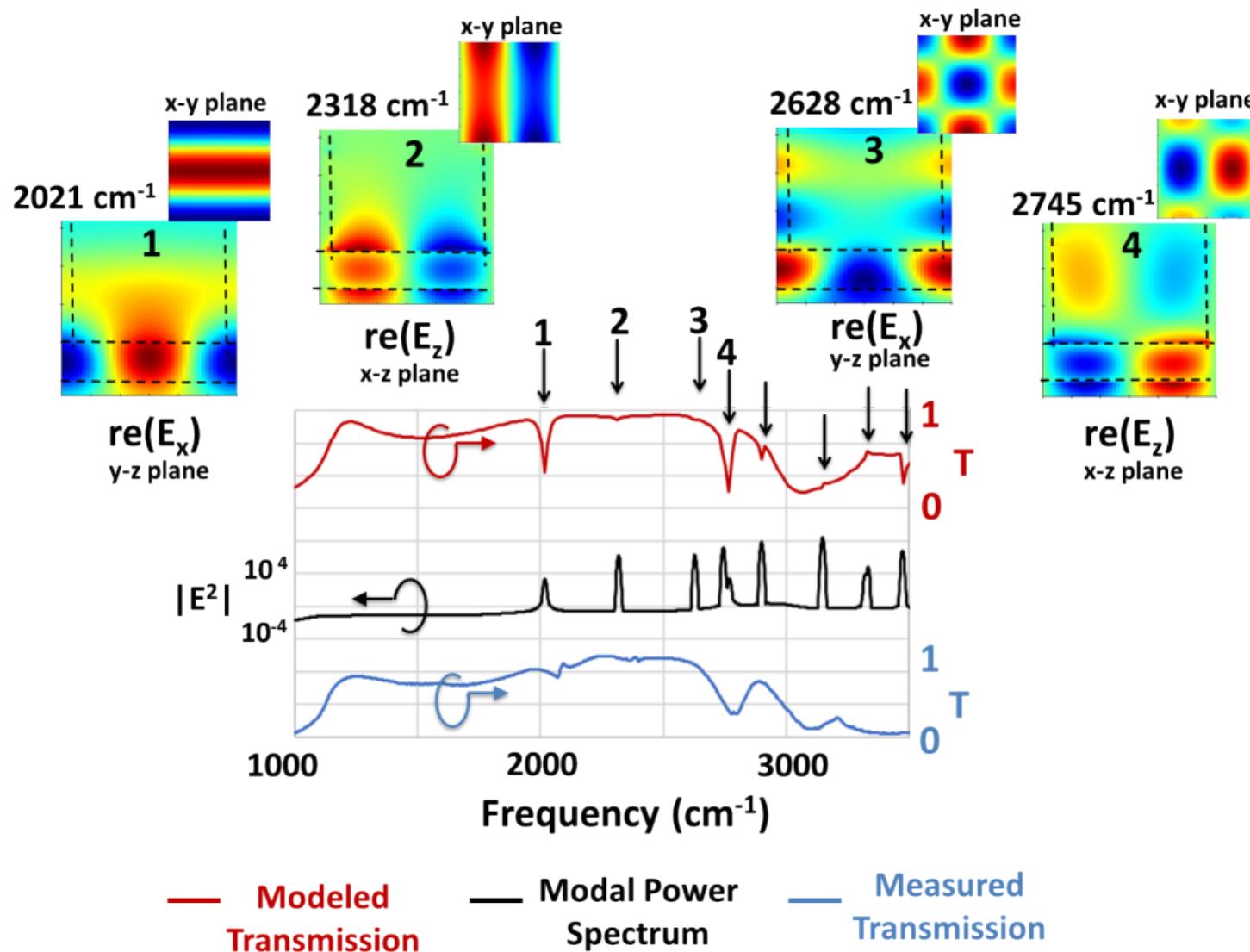


DB Burckel et. al., "Coupling between plasmonic and photonic crystal modes in suspended three-dimensional meta-films"
Opt. Exp. **28** (8), 10836-10846 (2020).

Analyzing the Scattering Spectrum : Empty Boxes



Analyzing the Scattering Spectrum: Empty Boxes



Coupling between Photonic Crystal Slab Modes and 3D Plasmonic Meta-atoms

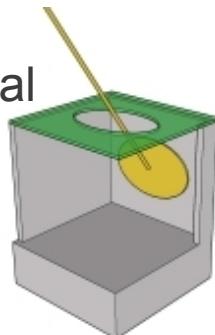
DB Burckel et. al., "Coupling between plasmonic and photonic crystal modes in suspended three-dimensional meta-films" Opt. Exp. **28** (8), 10836-10846 (2020).

Decorating with plasmonic meta-atoms

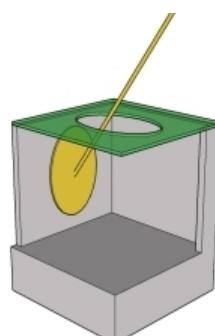


**Same Membrane Pattern
Different Evaporation
Direction**

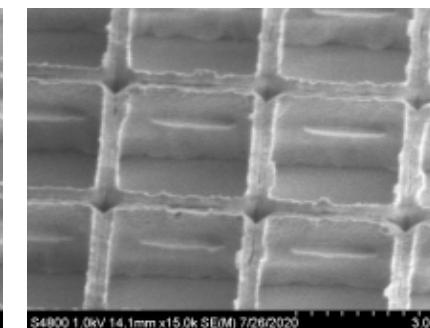
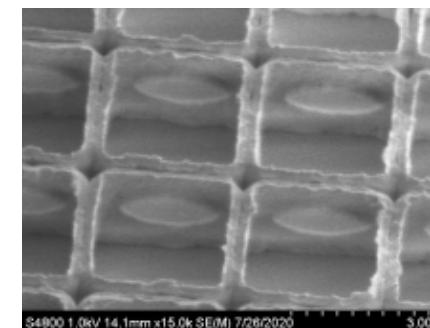
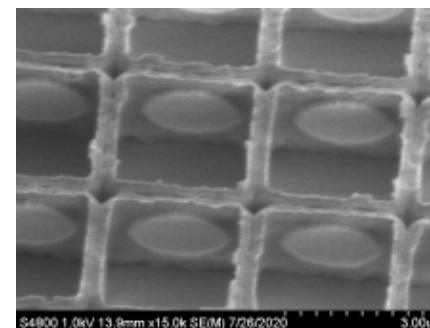
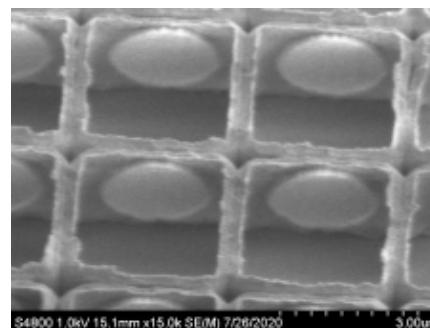
Horizontal
Ellipses



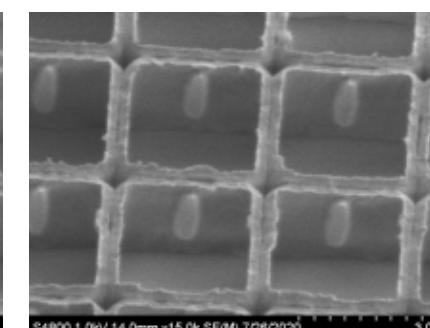
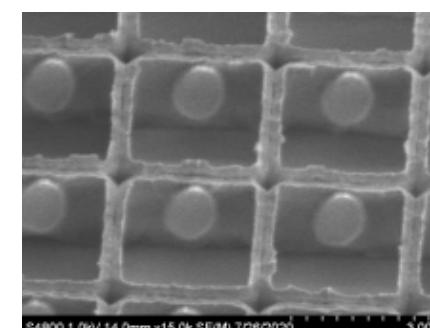
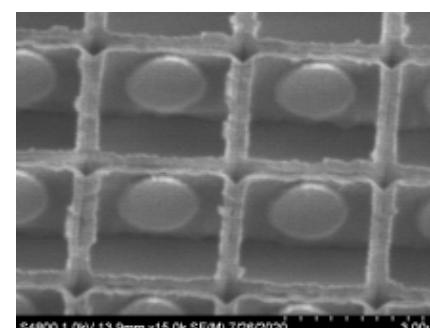
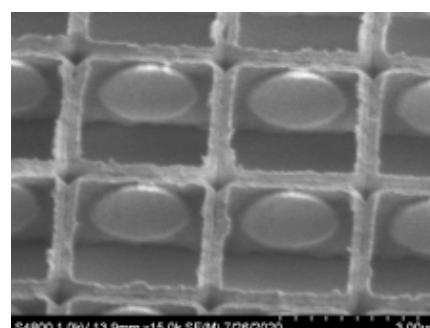
Vertical
Ellipses



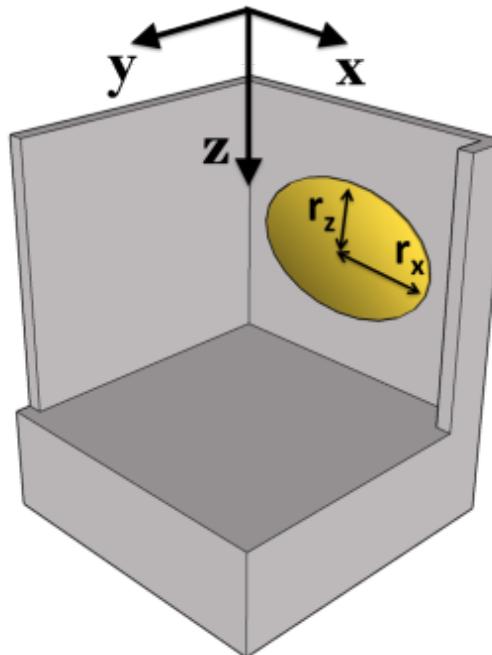
North wall evaporation



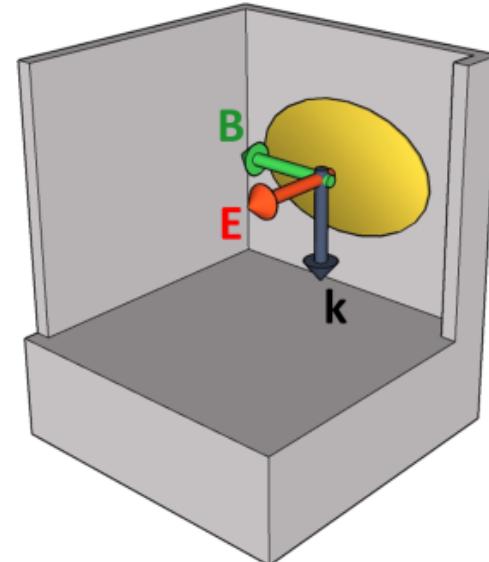
East wall evaporation



Polarization in 3D Metafilms

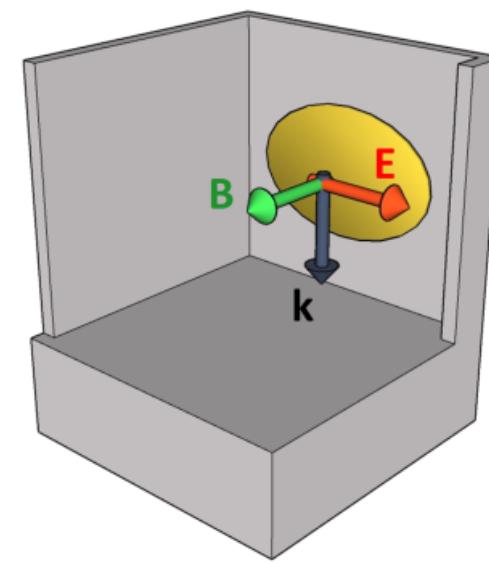


Transparent
Polarization



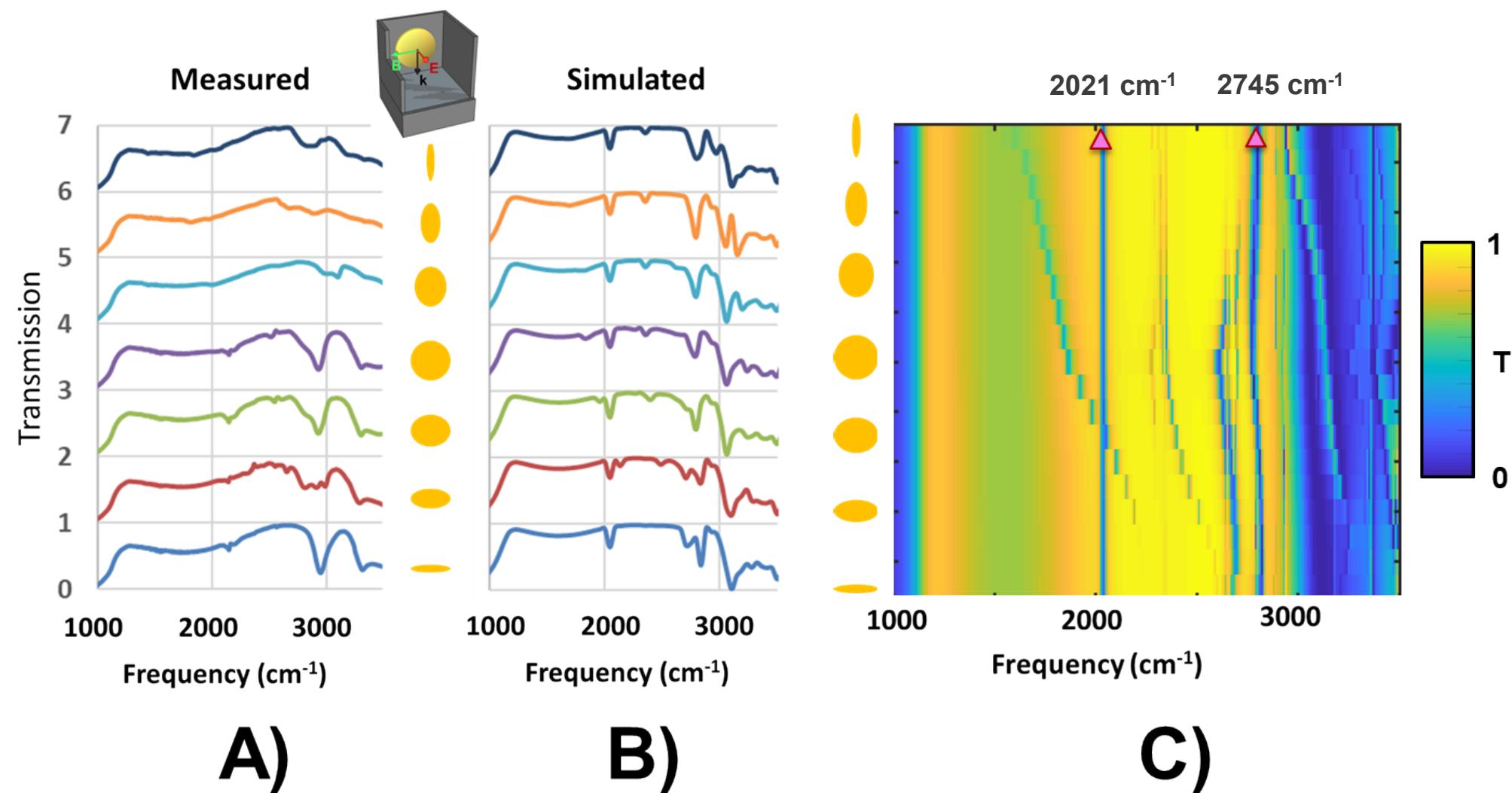
Electric field normal to
plane of ellipse

Resonant
Polarization

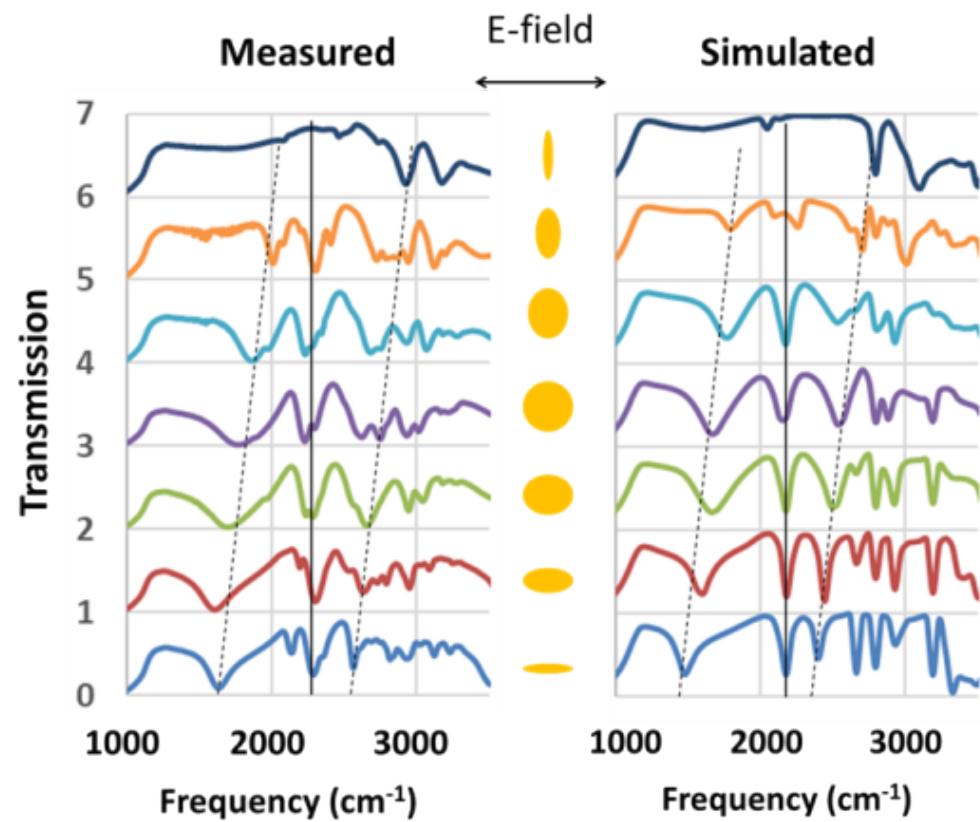


Electric field in the
plane of ellipse

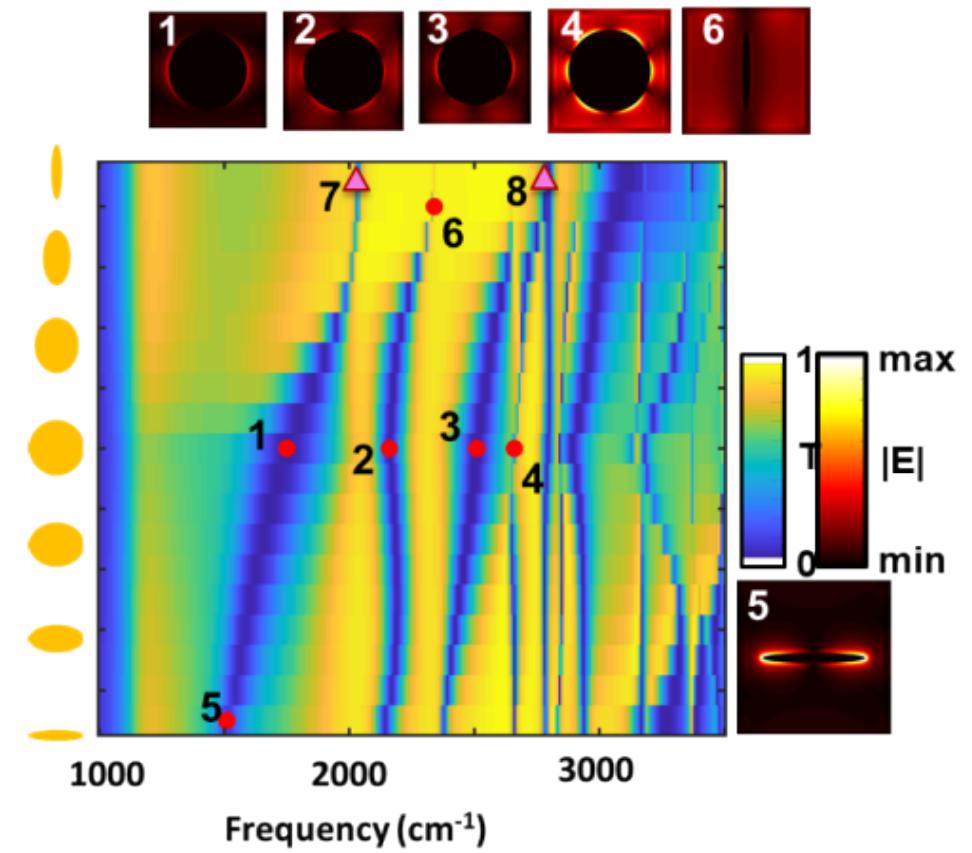
Transparent Polarization



Ellipses on the Floor



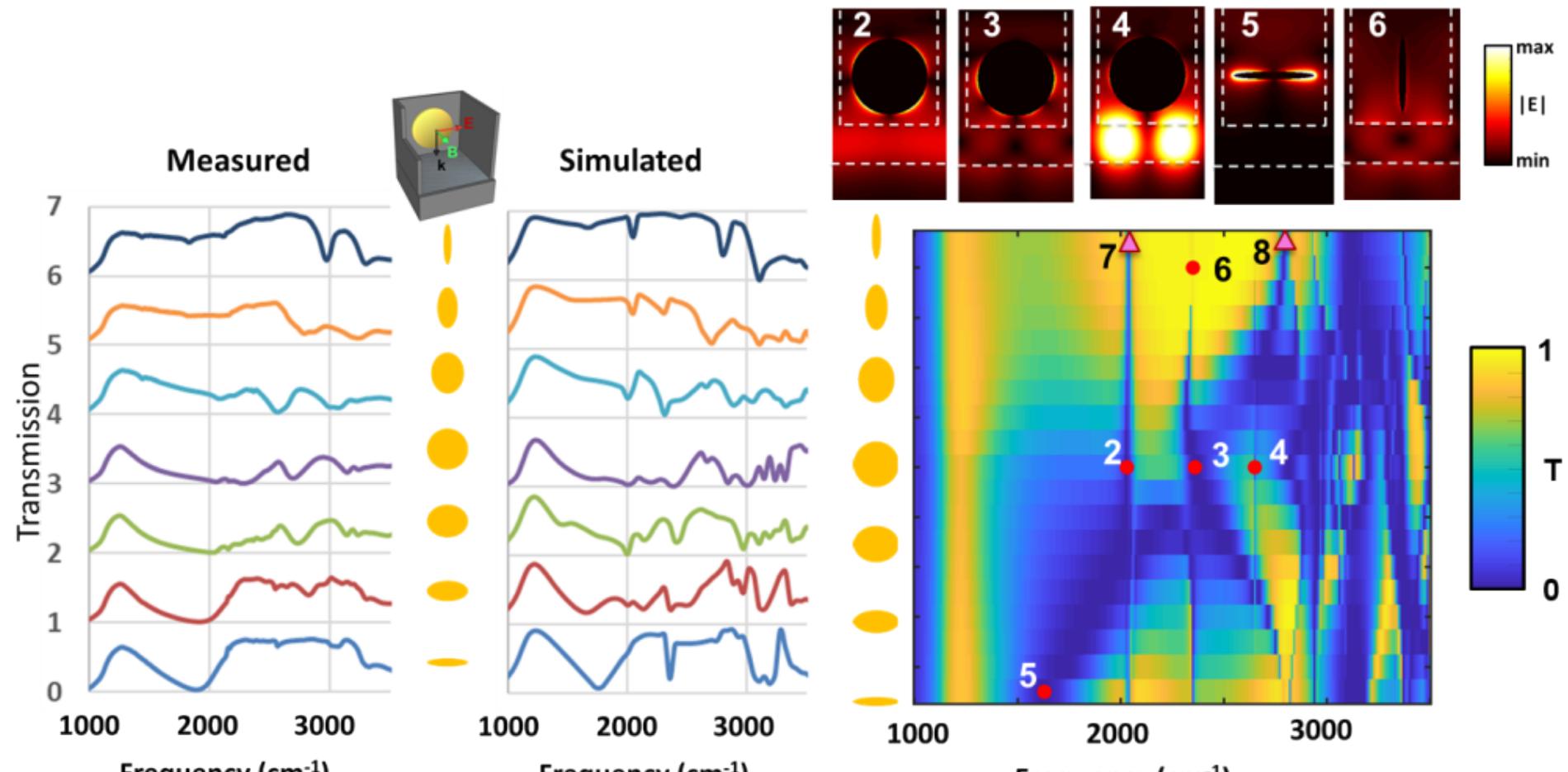
A)



B)

C)

Resonant Polarization



Conclusions

1. Wall-first membrane projection lithography fabrication approach is a robust method for creation of infrared 3D metafilms
2. 3D metafilms combine and couple photonic crystal slab modes and plasmonic particle modes
3. Planar ellipses on the floor respond to both incident polarizations
4. Vertical ellipses exhibit a resonant response to linear polarization with E -field in the plane of the ellipse, while being largely transparent to the orthogonal polarization
5. Retardation effects broaden the spectral width of resonances for vertically oriented ellipses.

Funding and Collaboration

- Funding : DARPA Extreme, NGA, SNL-LDRD
- SNL Collaborators: Michael Goldflam (Systems and Technology Research, San Diego, CA), Kate Musick, Michael Sinclair, Paul Resnick, Rob Jarecki
- External Collaborators: Gaspar Armelles -Microelectronic Institute of Madrid (IMM-CNM, CSIC) ;